

U.S. DEPARTMENT OF COMMERCE
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APPLICATION NO.

10/023,689

LIST OF REFERENCES CITED BY APPLICANT(S)
(Use several sheets if necessary)

APPLICANT

Makoto Ogusu et al.

FILING DATE

December 21, 2001

GROUP

2872

U.S. PATENT DOCUMENTS

*EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
	NONE					

FOREIGN PATENT DOCUMENTS

	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION YES/NO/ OR ABSTRACT
ku	JP 5-224398	09/03/93	Japan	—	—	Abstract
ku	JP 61-27505	02/07/86	Japan	—	—	Abstract
ku	JP 63-168601	07/12/88	Japan	—	—	Abstract

OTHER DOCUMENT(S) (Including Author, Title, Date, Pertinent Pages, Etc.)

ku	Y. Suzuki et al., "Gas Plasma Etching of Chromium Films," 21(9) Jap. J. Appl. Phys. 1328-1332 (1982).
ku	F.H.M. Sanders et al., "Selective Isotropic Dry Etching of Si ₃ N ₄ Over SiO ₂ ," 129(11) J. Electrochem. Soc. 2559-2561 (1982).
EXAMINER	Amel C. Laramie
DATE CONSIDERED	8/22/03

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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